

# ***Development of Ultrananocrystalline Diamond (UNCD) Coatings***

*Presented by*

*Jeffrey Elam  
Argonne National Laboratory*

*Materials, Sensors & Automation, and Glass Project Review  
June 21-24, 2004  
Arlington, Virginia*



Office of Science  
U.S. Department of Energy

**A U.S. Department of Energy  
Office of Science Laboratory  
Operated by The University of Chicago**



# Project Summary

---

- **Goal:**
  - Use UNCD to achieve significant energy savings in IOF industries
    - *First application – SiC multipurpose mechanical pump seals*
- **Challenge:**
  - Develop technology to take UNCD from laboratory to market application
    - *Need to mass produce UNCD coated parts*
- **Benefits:**
  - Improved wear resistance and corrosion resistance of UNCD coated parts
  - 20% energy savings of 236 trillion Btu by 2020 in pump applications primarily due to reduced friction losses
- **FY05 Activities:**
  - Commission and optimize 11-inch IPLAS system (up from 6-inch system)
    - *Demonstrate UNCD coating of multiple seals simultaneously*
  - Demonstrate benefits of UNCD coatings on gas seals
  - Verify tribological benefits of UNCD coated seals
    - *Perform long-term pump tests*

# ***Project Participants – Laboratory-led project***

---

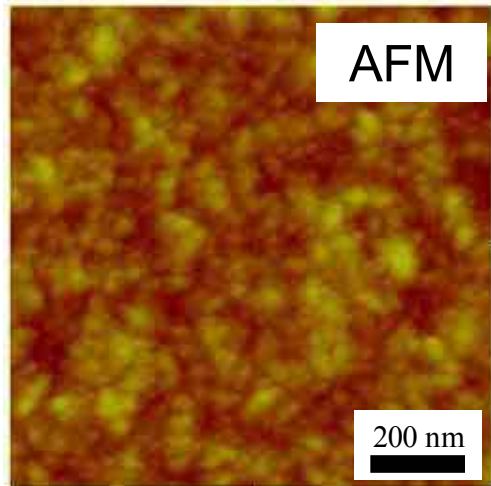
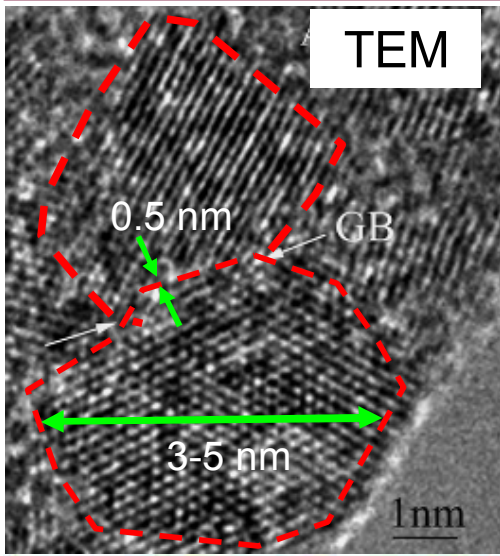
- **Argonne National Laboratory**
  - Energy Systems:
    - *Jeff Elam, John Hryn (Project POC), Joe Libera*
  - Energy Technology:
    - *Ali Erdemir, Andriy Kovalchenko*
  - Materials Science:
    - *Orlando Auciello, John Carlisle, Dieter Gruen, Mike Pellin, Alex Zinovev*
- **Industry Partners:**
  - Advanced Diamond Technologies, Inc. (ADT)
    - *Neil Kane (Industry POC)*
  - John Crane, Inc.
  - IPLAS Innovative Plasma Systems
  - Morgan Advanced Ceramics
  - Northwestern University
  - University of Illinois at Chicago

# **Barriers – Pathways – Critical Metrics**

---

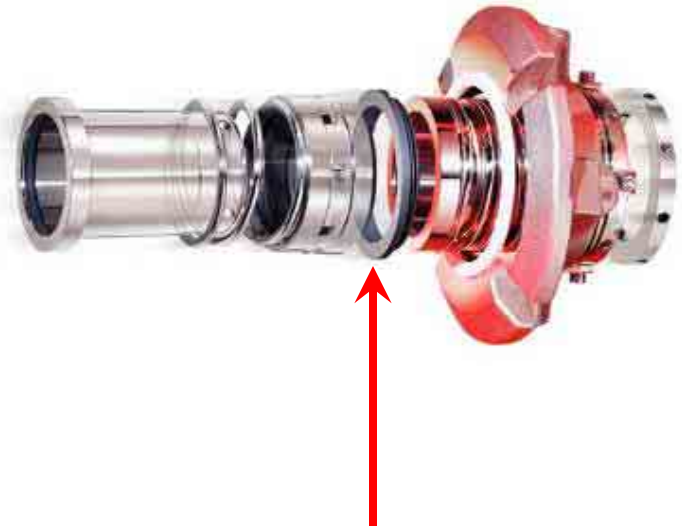
|  |   |   |
|--|---|---|
| <b>1) Uniform nucleation and growth of UNCD</b><br>1) <i>smooth films</i><br>2) <i>good adhesion</i> | <b>Understand plasma deposition and surface seeding requirements, UNCD characterization and testing</b> | <b>Develop seeding protocol to produce uniform UNCD films</b><br><b>(COMPLETED)</b> |
| <b>2) Scale – up UNCD deposition process</b>   | <b>Commission 11-inch plasma system</b>   | <b>Multiple seals coated with UNCD simultaneously</b>                               |
| <b>3) Limited seal testing facilities</b>  | <b>Use industrial facilities and expand lab capabilities</b>  | <b>Perform successful pilot test (data indicate energy savings)</b>                 |
| <b>4) Commercialization of UNCD technology</b>   | <b>Launch company (ADT)</b>   | <b>Sign toll-processing agreement</b>   |

# Ultrananocrystalline Diamond (UNCD) Properties



- Hardness - 97 GPa
  - Elastic Modulus - 970 GPa
  - Fracture Strength - 5 GPa
- Grain Size - 2 - 5 nm
  - RMS Roughness - 0.5 - 1  $\mu$ -inch
  - Friction Coefficient - 0.03

# ***UNCD for Multipurpose Mechanical Pump Seals***



**UNCD Coating**



- **UNCD to reduce friction and eliminate wear**

# ***Technical Barrier #1: Uniform nucleation and growth of UNCD***

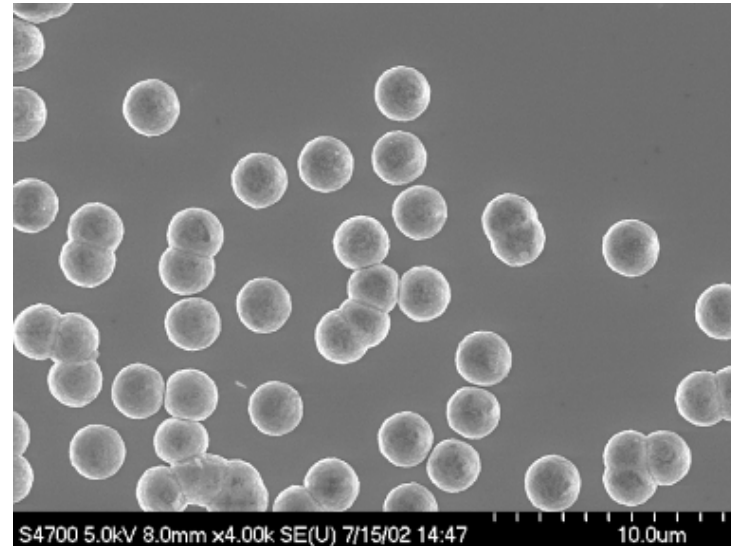
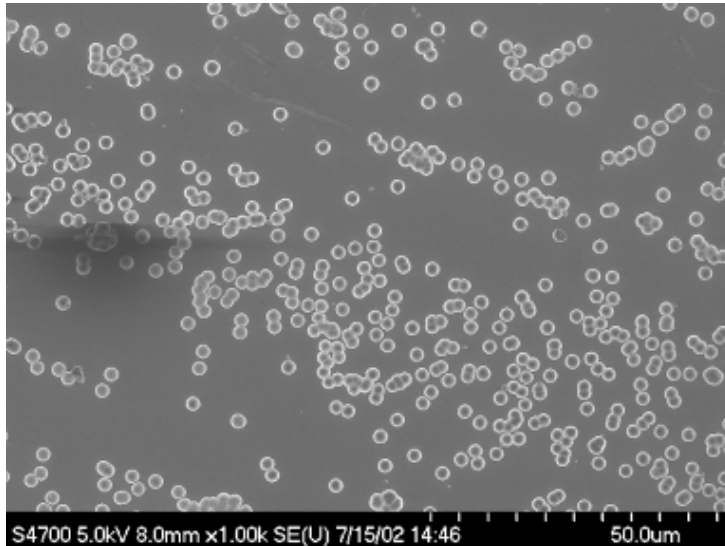
---

- **Seeding to achieve smooth UNCD films**
- **Seeding to achieve excellent adhesion of UNCD to SiC Seal**

# UNCD – Example of Poor Seeding

---

Sample: Unseeded CVD SiC



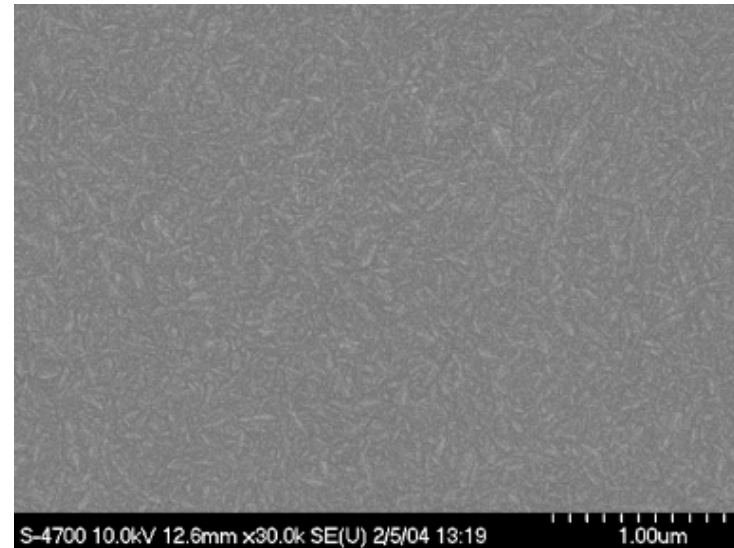
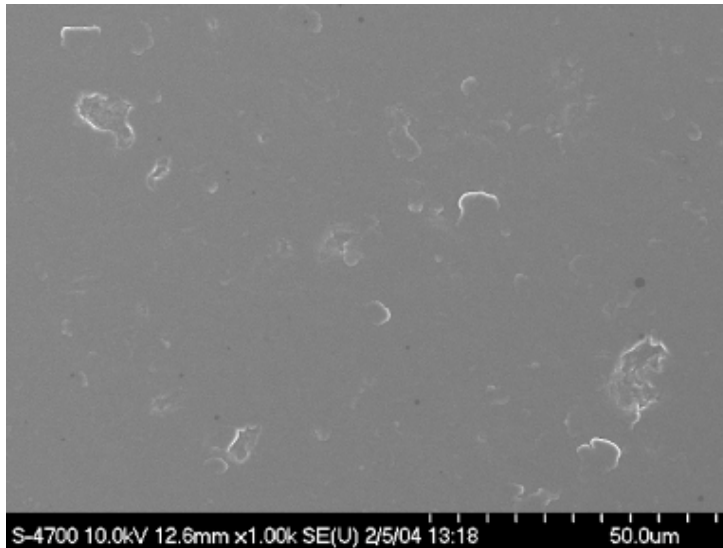
- Low nucleation density – discontinuous coating



# ***UNCD – Example of Excellent Seeding***

---

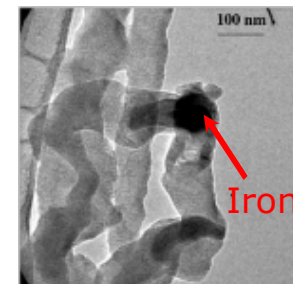
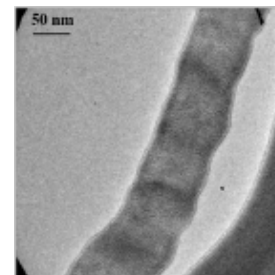
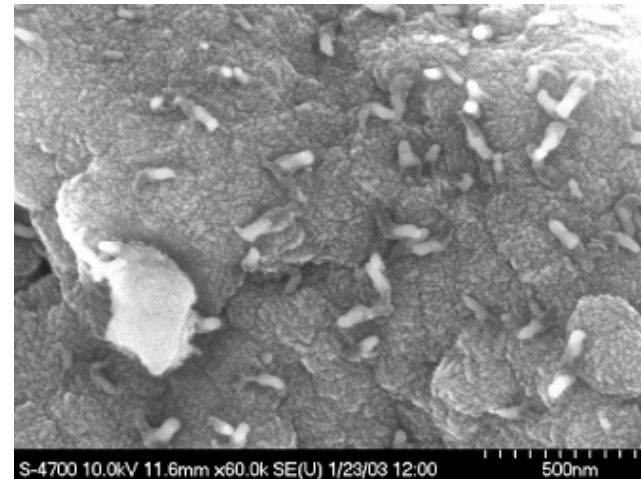
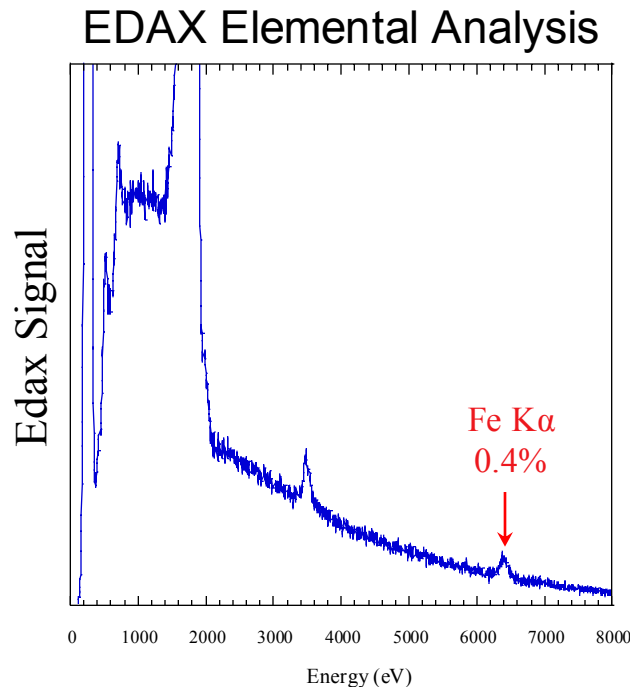
Sample: Mechanically Seeded  $\alpha$ -SiC



- High nucleation density - dense, continuous, smooth film

# Simultaneous UNCD and Carbon Nanofiber (CNF) Growth

SEM and TEM Following UNCD Treatment



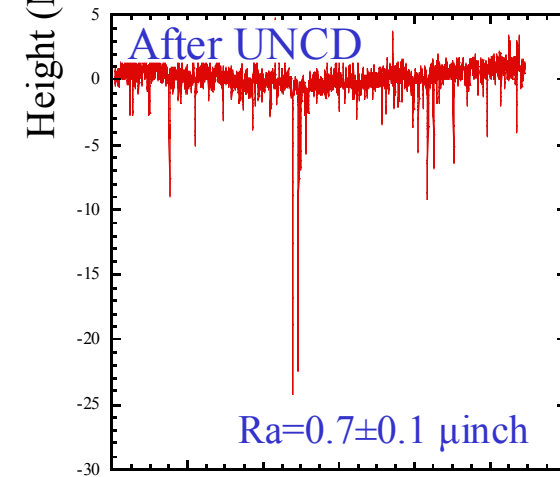
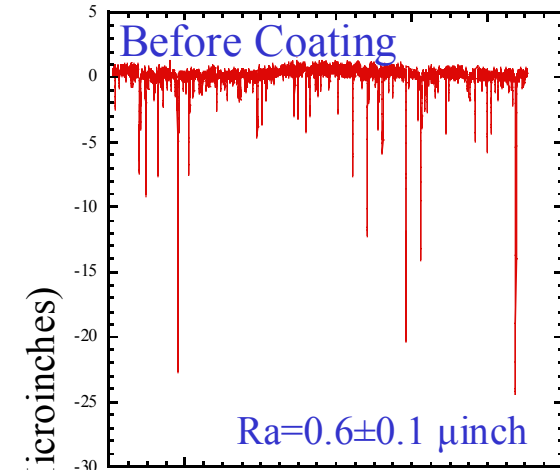
SEM, TEM shows CNF with iron particle catalyst

- Trace Fe Contamination Catalyzes CNF Growth
- Developed Screening Process for Iron

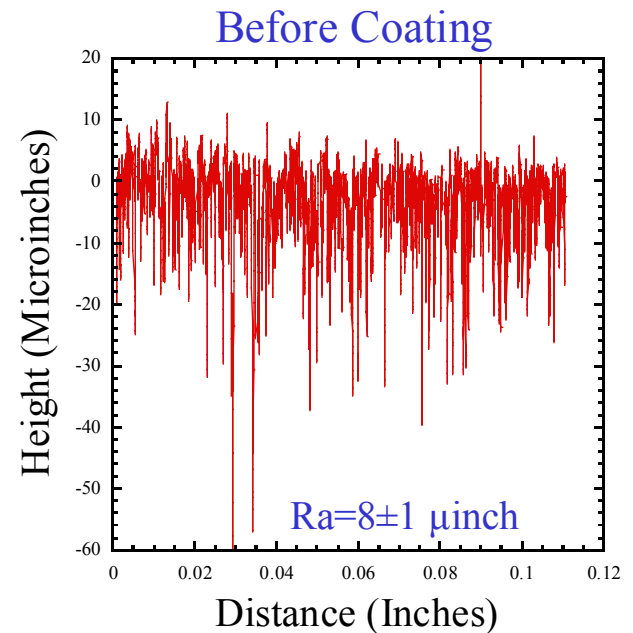
# UNCD Coating of Smooth 2" OD $\alpha$ -SiC Seals



SEM of Uncoated Seal

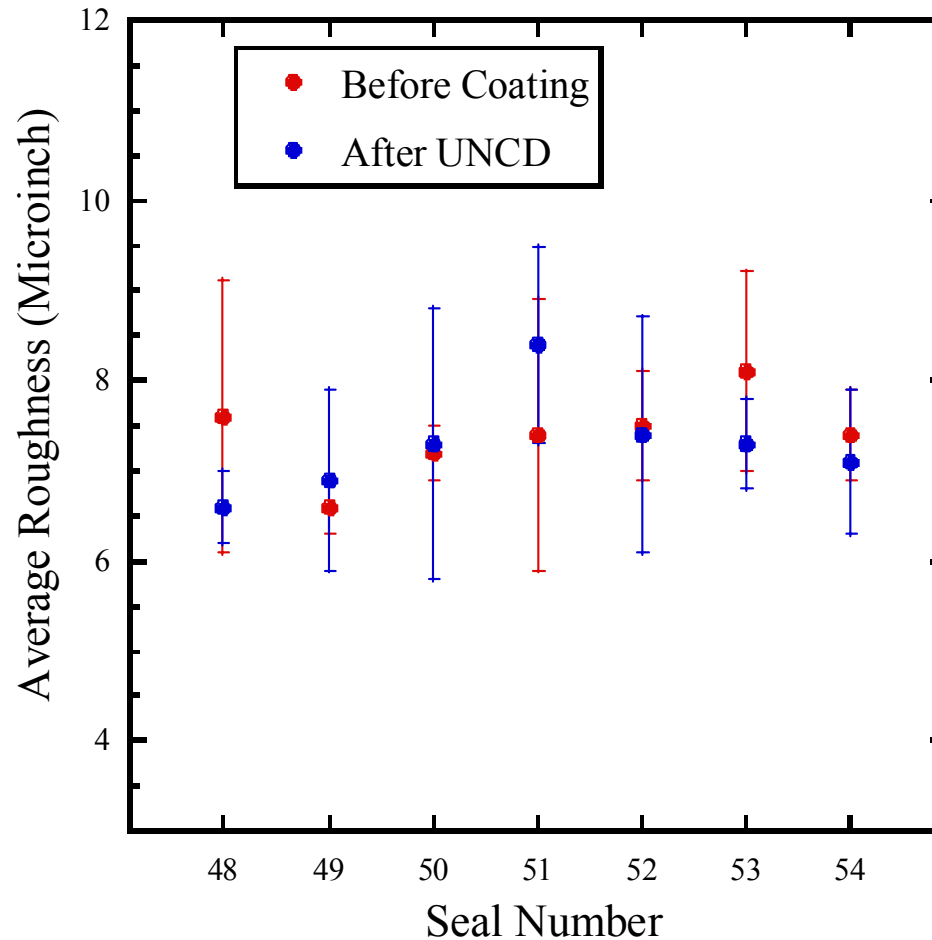


# ***UNCD Coating of Rough 1" OD $\alpha$ -SiC Seals***



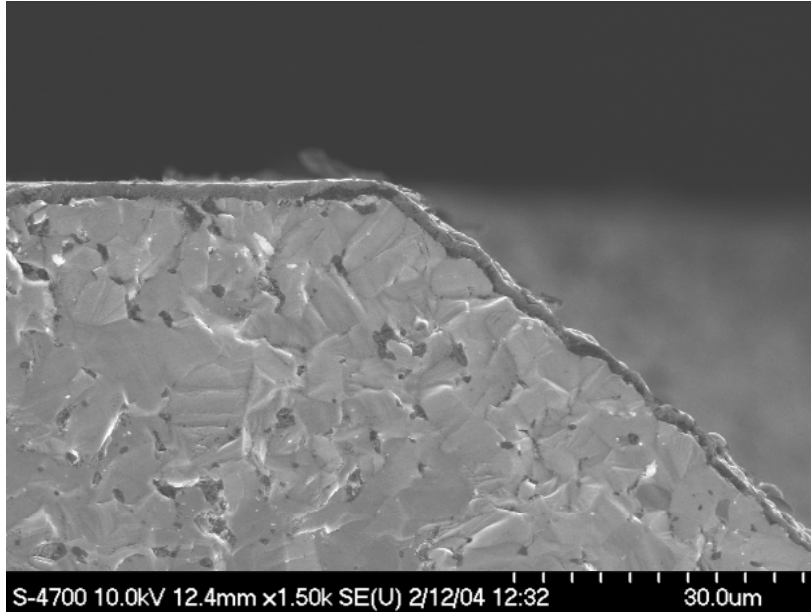
- Rough initial surface for 1" seals

# Roughness Measurements of Rough 1" OD Seals Following UNCD Coating

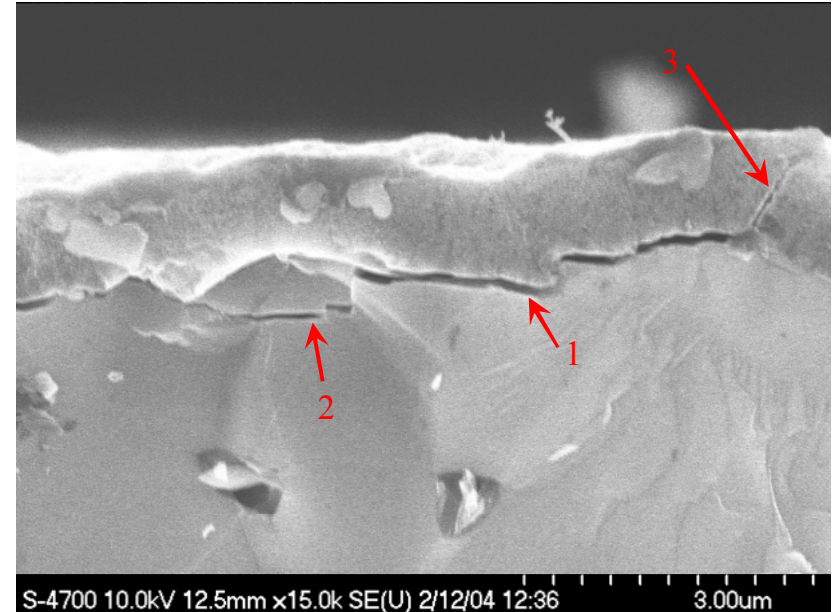


- No roughness change from UNCD Coatings

# Adhesion Measurements Using Fracture Analysis



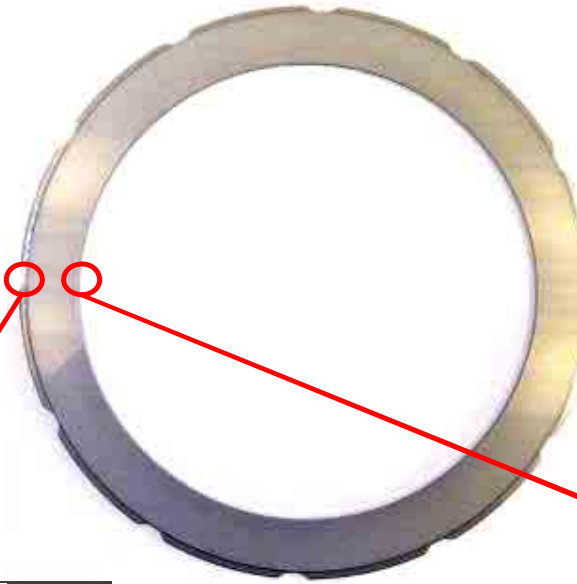
Conformal UNCD coating over  
Seal face and beveled edge



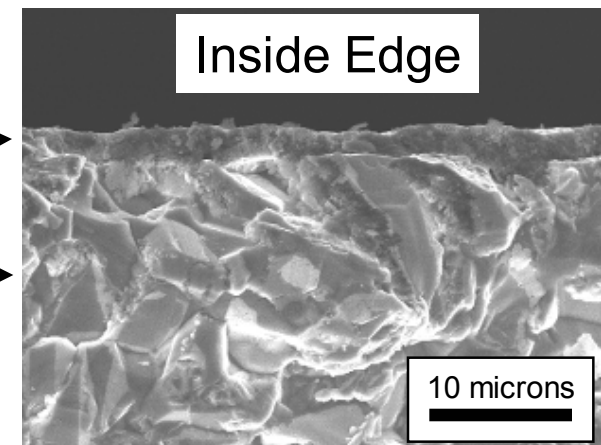
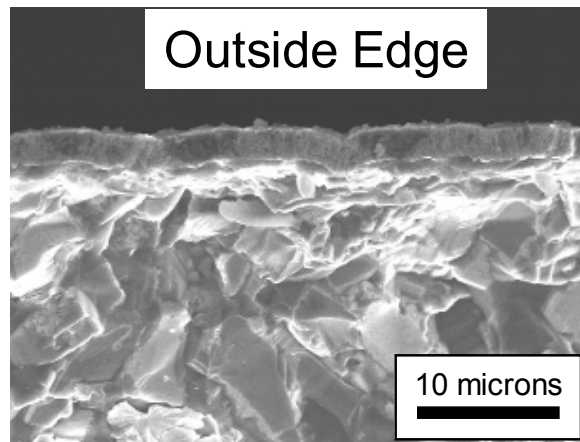
Fracture of UNCD-SiC interface observed after  
diamond saw cutting (1). However, fracture also  
observed along SiC grains (2) and UNCD film (3)

# UNCD Coating of 5" Gas Seals

- Improved coating technology required for 5" gas seals
- Coating must preserve precisely engineered taper



- Segment of 5" seal was coated in existing small-area plasma system



UNCD

SiC

- UNCD Maintains Critical Tolerance Across Face of 5" Gas Seal



# Technical Barrier #2: Scale – up UNCD deposition process

---

## *IPLAS 11” Microwave Plasma CVD System*



- First unit of its kind in the world
- Will enable batch-coating of multiple 2” seals
- Will enable coating of intact 5” seals

- Work is underway to install and commission this system



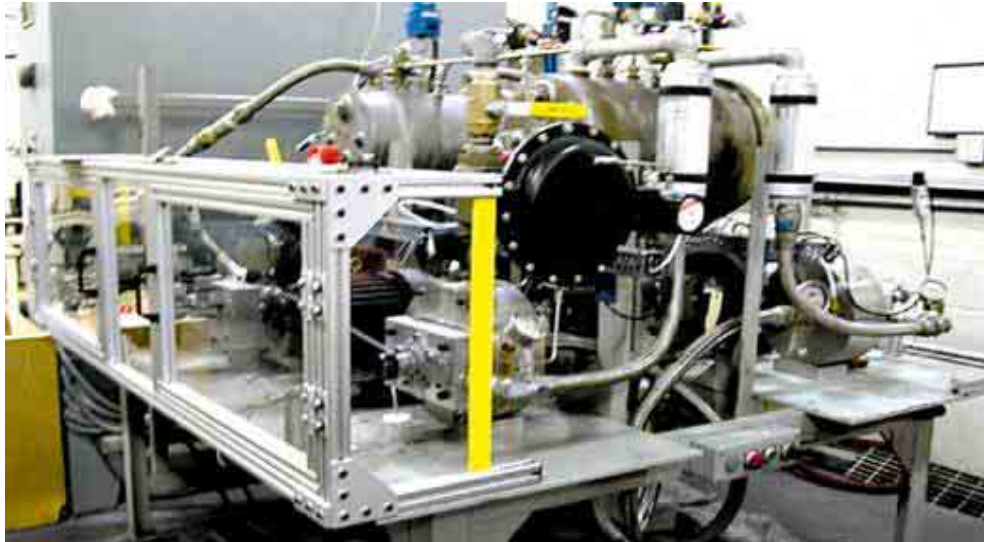
# ***Technical Barrier #3: Limited seal testing facilities***

---

- **Building Test Pump Loop at Argonne for Measuring Seal Friction and Wear**
- **Installed Surface Profiler at Argonne**
- **Friction and Wear Analysis at John Crane Testing Facilities**

# ***Hot Water Test of UNCD-Coated Seals at John Crane***

---

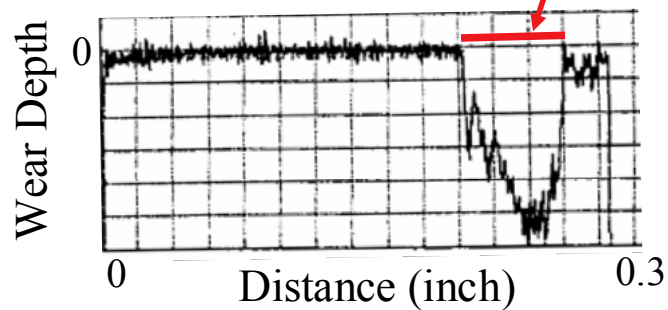
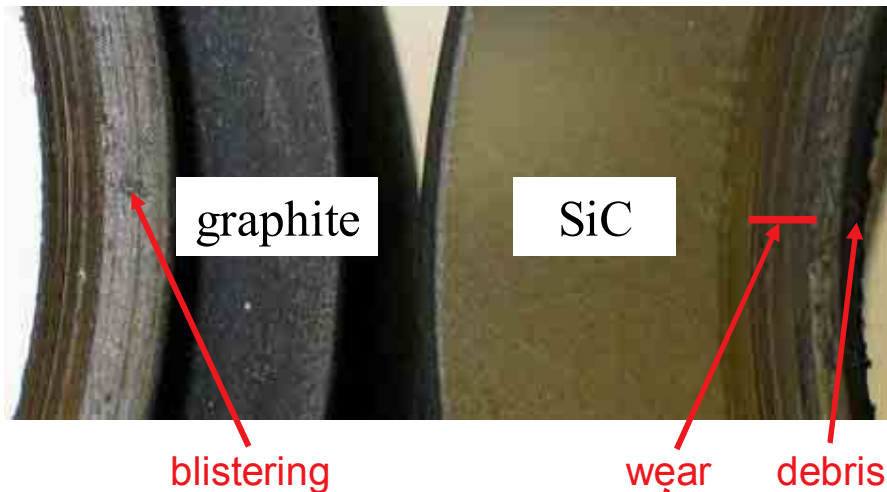


- 2" OD Seal
- 100 Hours

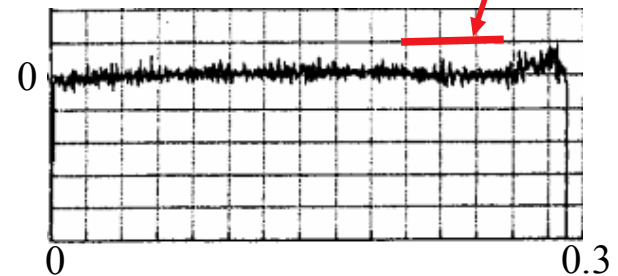
- Very aggressive test of materials properties
- Mimics harsh conditions in chemical process pump
- 100 hour test simulates 2 years of extreme use

# Hot Water Test of UNCD-Coated Seals

Uncoated

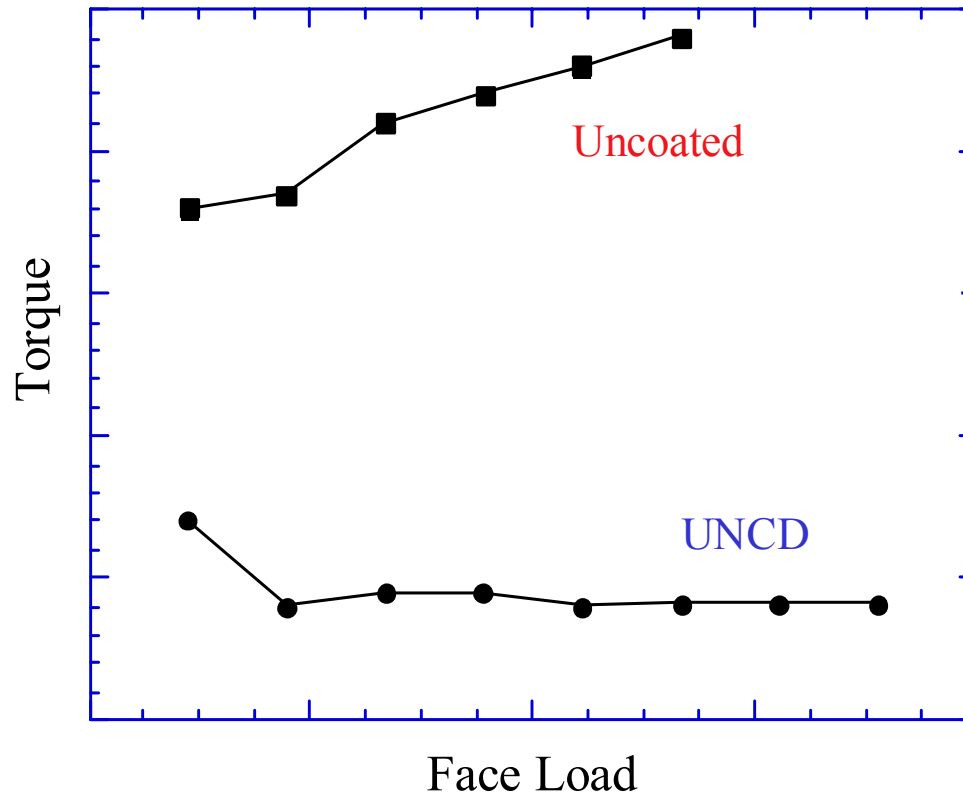


UNCD-Coated



# Friction Measurements of UNCD Coated 2" SiC Seal

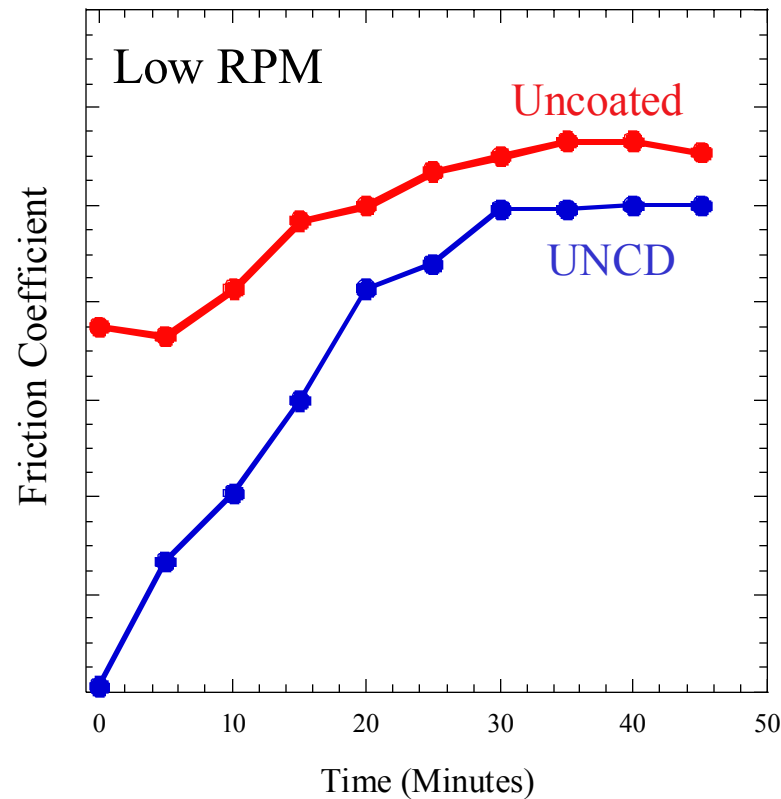
Low Initial Roughness



- Significantly Reduced Friction for Smooth Seal Surface

# Friction Measurements of UNCD Coated 1" SiC Seal

High Initial Roughness



- Marginally Reduced Friction for Rough Seal Surface

➡ Current Study: Effect of Roughness on UNCD Friction

# ***Technical Barrier #4: Commercialization of UNCD technology***

---



- **Advanced Diamond Technologies**
  - Argonne-initiated start-up company
    - *Exclusive license in UNCD application*
  - Company officially launched in 2003
  - Business plan established
  - Toll processor for seal manufacturers
    - *Agreements in principle reached with partners*

# ***Future Work Leading to Commercialization***

---

- **FY05**

- Understand effect of initial substrate roughness on UNCD friction
- Commission and optimize 11-inch IPLAS system (up from 6-inch system)
  - *Demonstrate UNCD coating of multiple 2" seals simultaneously*
- Demonstrate benefits of UNCD coatings on gas seals
- Verify tribological benefits of UNCD coated seals
  - *Perform long-term pump tests*

- **FY06-07**

- Pilot tests (field tests): 2" seals, 5" seals
- Automation of UNCD deposition process

- **FY07**

- Commercialization (sign toll-processing agreements)
- Final report